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Notice of Allowability	Application No.	Applicant(s)
	10/810,759	11157.01
	Examiner	LU ET AL. Art Unit
		, at one
	Chuong A. Luu	2818
The MAILING DATE of this communication apper All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGOT (of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in to or other appropriate commun GHTS This application is au	his application. If not included
1. This communication is responsive to <u>9/19/2007</u> .		
2. The allowed claim(s) is/are <u>1,3-6,8-10,12-15 and 17-20</u> .		
<ul> <li>3. ☐ Acknowledgment is made of a claim for foreign priority under a) ☐ All b) ☐ Some* c) ☐ None of the:</li> <li>1. ☐ Certified copies of the priority documents have</li> <li>2. ☐ Certified copies of the priority documents have</li> </ul>	been received.	
2. Certified copies of the priority documents have been received in Application No  3. Copies of the certified copies of the priority decuments have been received in Application No		
3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONMETHIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a ENT of this application.	reply complying with the requirements
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
5. CORRECTED DRAWINGS ( as "replacement sheets") must be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached		
1) ☐ hereto or 2) ☐ to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the	e neader according to 37 CFR 1	.121(d).
5. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s)		
I. ☐ Notice of References Cited (PTO-892)	5. Notice of Inform	nal Patent Application
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Sumr	
B. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date	Paper No./Mai 7.	il Date
L ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. ⊠ Examiner's Sta	tement of Reasons for Allowance
,	9. 🗌 Other	
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## **DETAILED ACTION**

## REQUEST FOR CONTINUED EXAMINATION (RCE)

The request filed on September 19, 2007 for a Request For Continued

Examination (RCE) under 37 CFR 1.53(d) based on parent Application No. 10/810,759 is acceptable and a RCE has been established. An action on the RCE follows.

## Allowable Subject Matter

Claims 1, 3-6, 8-10, 12-15 and 17-20 are allowed.

The following is an examiner's statement of reasons for allowance: The examiner has reviewed the prior art in light of applicant's claimed invention and finds that the combined claims define over the prior art. The cited prior art does not disclose or suggest a semiconductor device inter alia the limitations "...forming a first silicidation metal in contact with said source/drain regions, said protective layer separating said polysilicon gate electrode from said first silicidation metal; forming a blocking layer over said source/drain regions step from said first silicidation metal, said blocking layer comprising a metal silicide; removing said protective layer from over said polysilicon gate electrode after forming said blocking layer; forming a second silicidation metal in contact with said polysilicon gate electrode and in contact with said blocking layer; and siliciding said polysilicon gate electrode using said second silicidation metal to form a silicided gate electrode said blocking layer protecting said source/drain regions from said siliciding. ..."

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.Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chuong A. Luu whose telephone number is (571) 272-1902. The examiner can normally be reached on M-F (6:15-2:45).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Steven H. Loke can be reached on (571) 272-1657. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000

CHUONG LUU PRIMARY EXAMINER